

(19)  
(12)

(KR)  
(A)

(51) 。 Int. Cl.<sup>7</sup>  
H05B 33/10

(11)  
(43)

2003-0081737  
2003 10 22

(21)

10-2002-0020102

(22)

2002 04 12

(71)

20 LG

(72)

299-24

(74)

:

(54)

E L

EL ,

가 ,

EL ,

4

1a 1d EL .

2a 2d EL

3a 3d EL

4	3				R, G, B	.
5a	5h					EL
6					.	
7a	7c	6		A	.	
8					EL	
9	8	'B'			R, G, B	.

\*

10 :	20 : 1
20-1 : 1	20-2 : 2
30 :	40 :
50 :	60 :
60-1 :	60-2:
70-1 : R	70-2 : G
70-3 : B	90 : 2

[illegible]

1b 1d 1a EL

(B) , 1c (delta) , 1d (R) R 1b (G)

가 ITO ( ) 가 가 . ,

1b (6)가 (6) , 가

1b 2a 가 ,

2a 2d , EL

R, G, B 2 , 6 6

, R, G, B 3 1b, 1c, 1d (6) , 6 6

, 3a 3d EL

3a (6-1) (6) 1b (mask hole) , R · G · B 1

4 3 (6) R, G, B .

4 (6-1) (6) 가 (6-1) a .

(6-1) (6) ,

(6-1) .

EL

EL

가



(40) (pixel) 가 , (a) (b)

(a) 가 .

가 (50)

(10) 1 (20) 2 ( ) R, G, B

6 (60) (60) 3 (60-1)가

(hole) (60-2) (60-2) 가 (60-1) (60-2)

(60-1)

7a 7c 6 A (60-1) 4a (60)

4b 4c

(60-1) (a) (b) 1~1000 $\mu$ m (a)

(10) R, G, B R, G, B ( )

5d 5f (60) 3 (align) R, G, B

5g R, G, B (70-1, 70-2, 70-3)

R, G, B (60) R, G, B

5h (Mg-Ag , Al )

2 (90)

( , ) ( )

5a 5g (stack) EL TFT 8 AM(Active Matrix)

-EL

8 (40) 1 (20) (a)

(b)

(a) (60-1)가

9 8 'B' (60) R, G, B (70-1, 70-2, 70-3)

EL 가

1 ( ) , , 1 1 , 2 1 (uniformity) , 가 .

가

(57)

1.

가

2.

1

3.

1

4.

1

5.

1

6.

1

7.

1

1~1000 $\mu$ m

8.

1

2

EL

R, G, B

1 ;

1

가

1

1

;

1

;

1

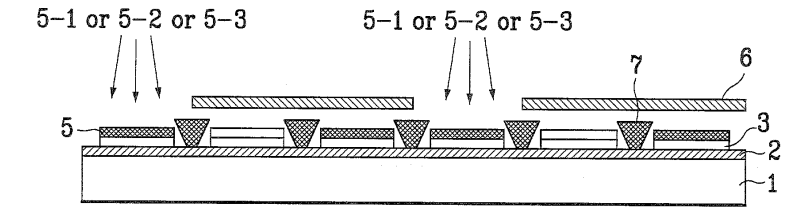
가

R, G, B

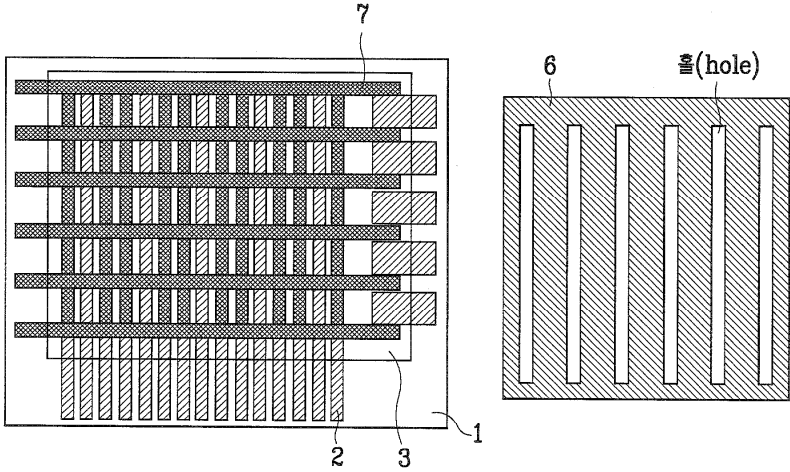
;

- EL . 1 2
9. 1~1000μm EL .
- 8 10. 1 EL 1
- 8 11. 3 R, G, B EL 1
- R, G, B

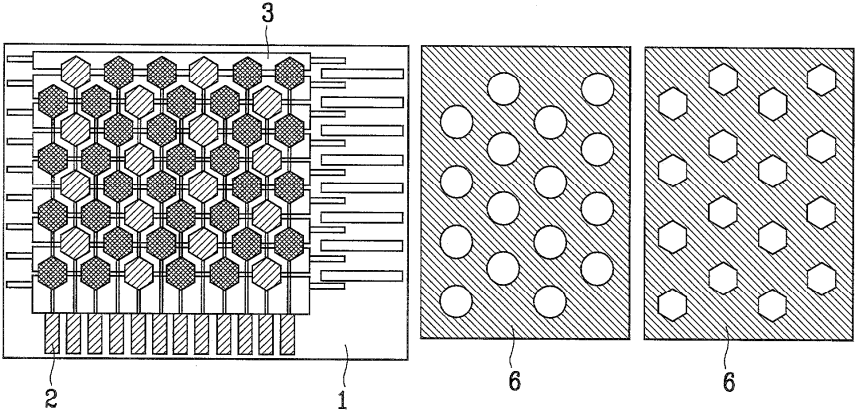
1a



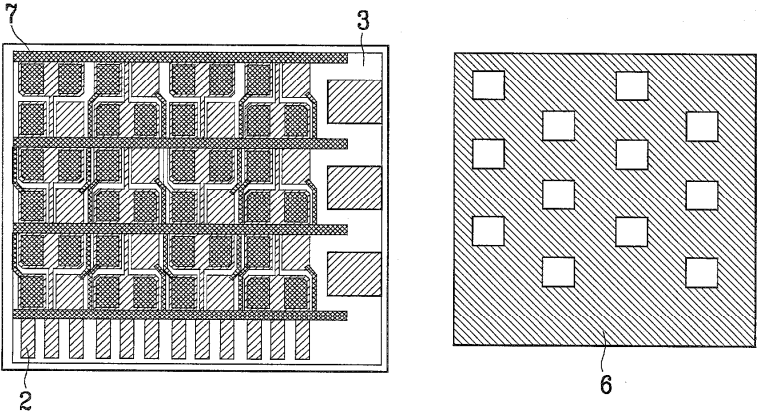
1b



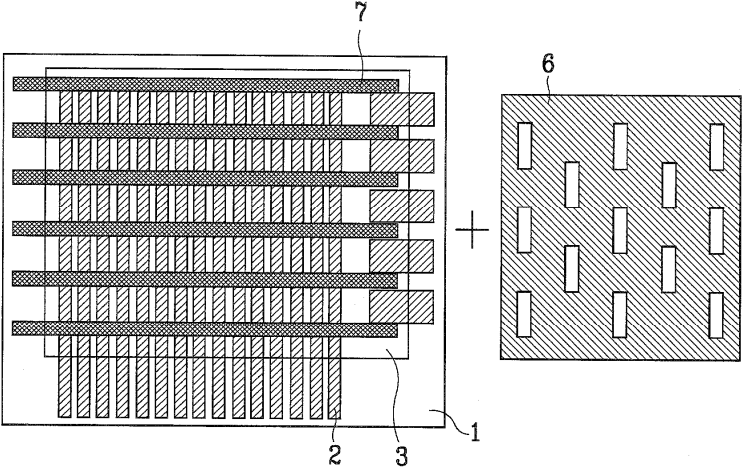
1c



1d

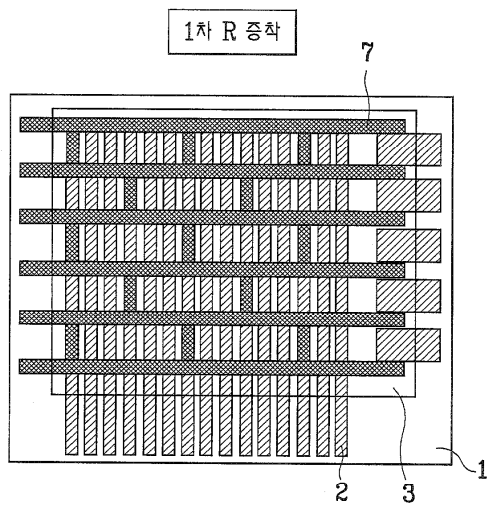


2a

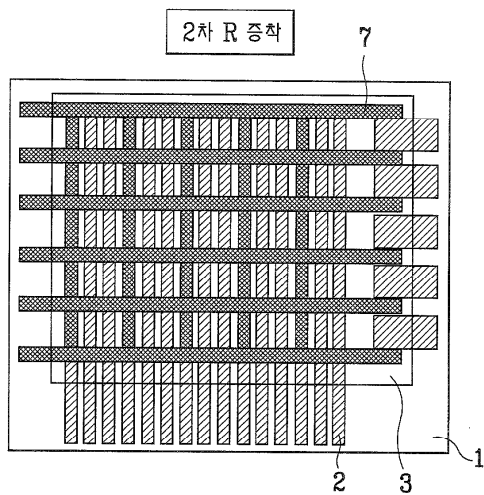




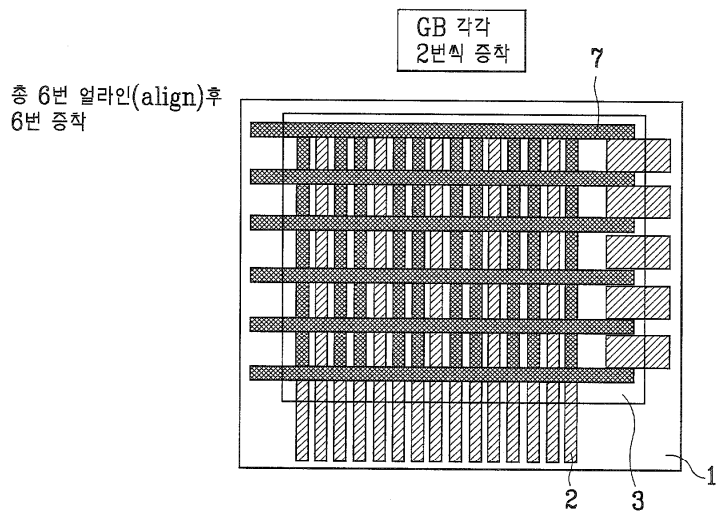
2b



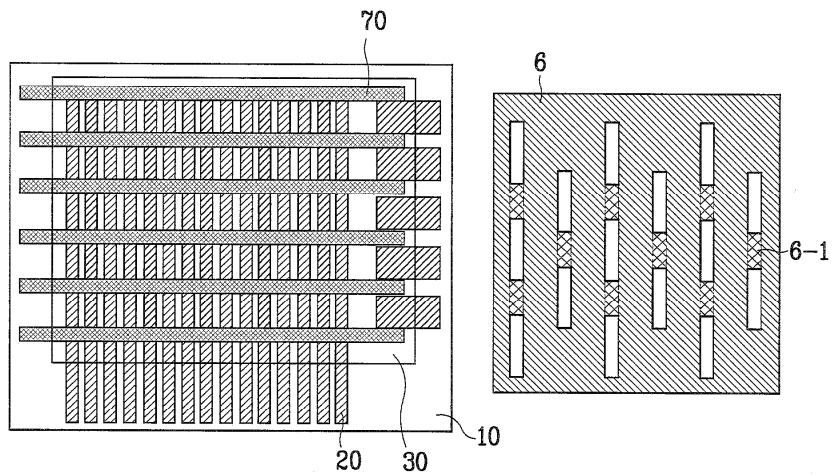
2c



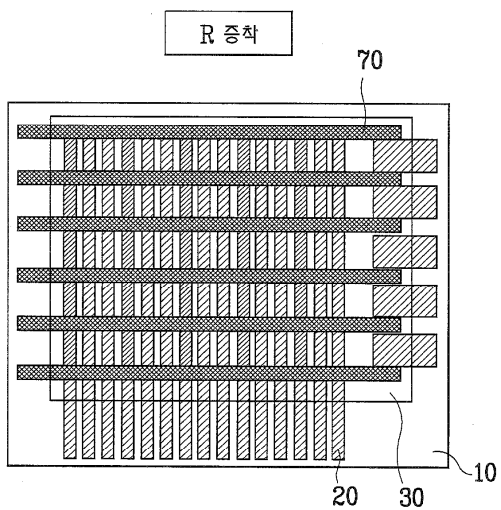
2d



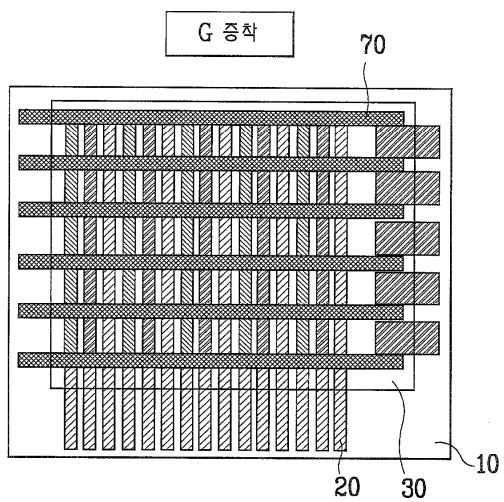
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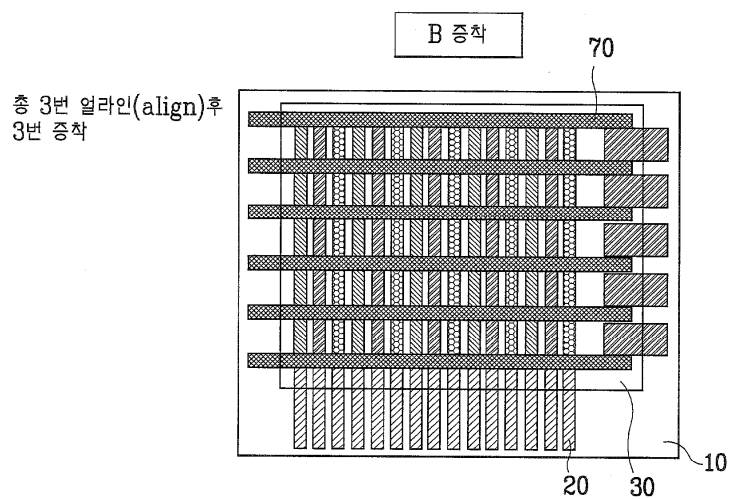
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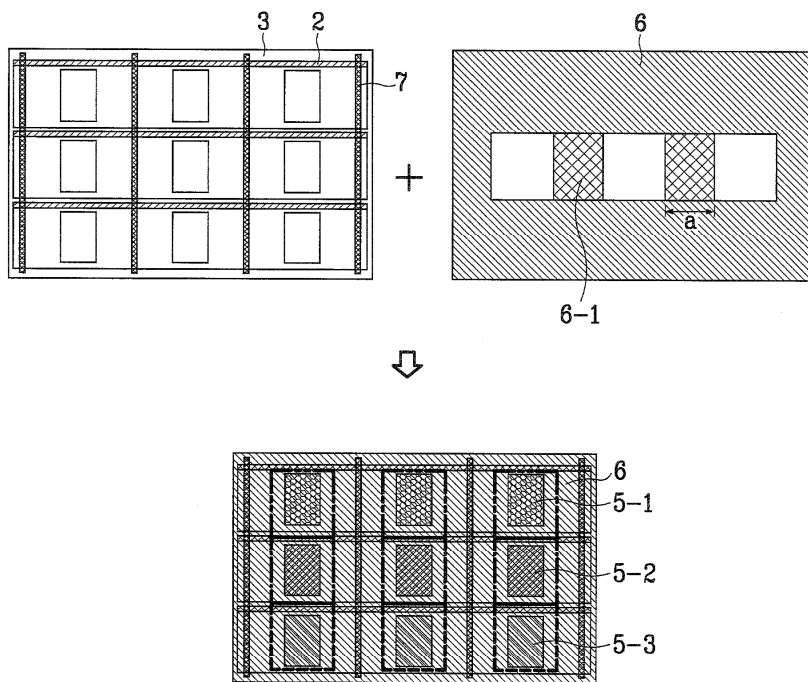
3c



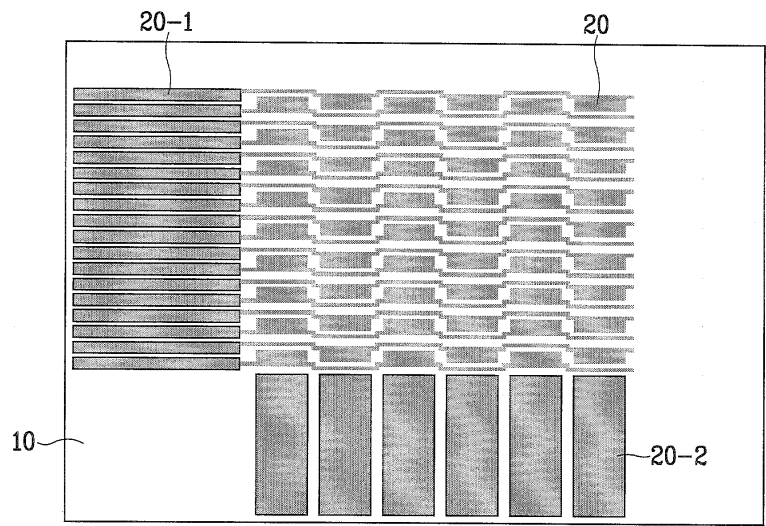
3d



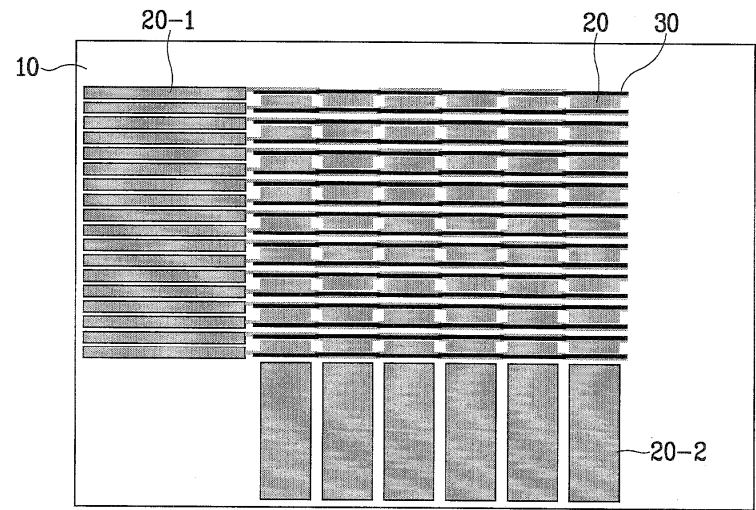
4



5a

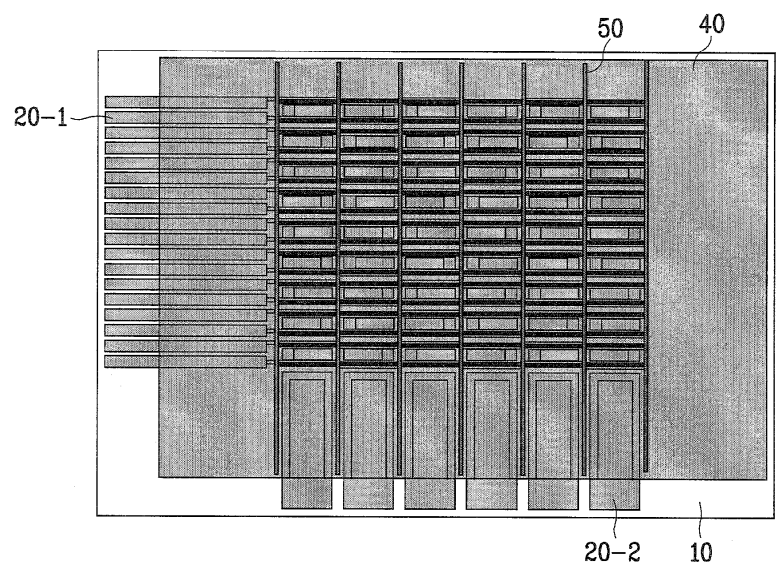


5b

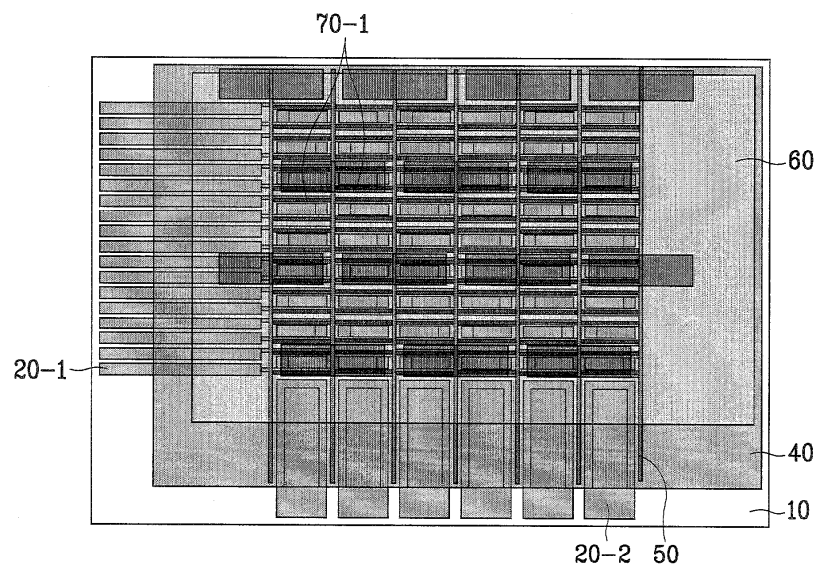




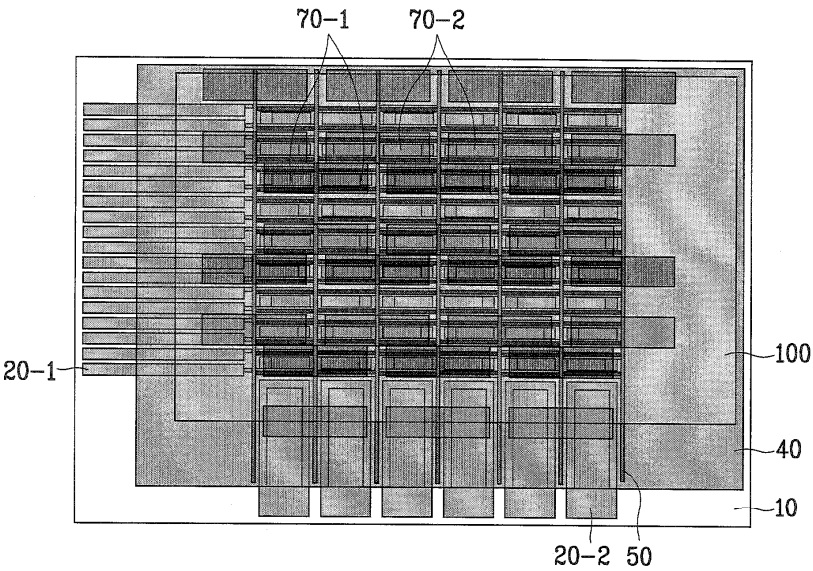
5c



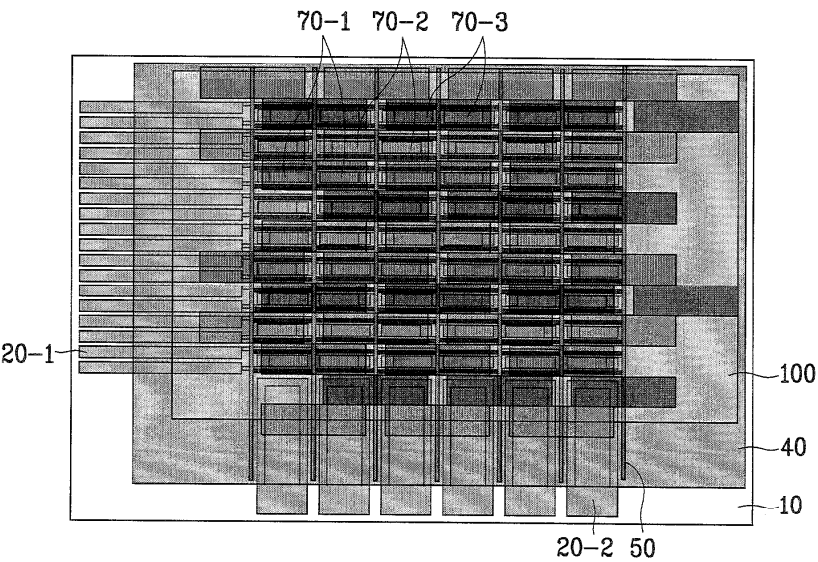
5d



5e

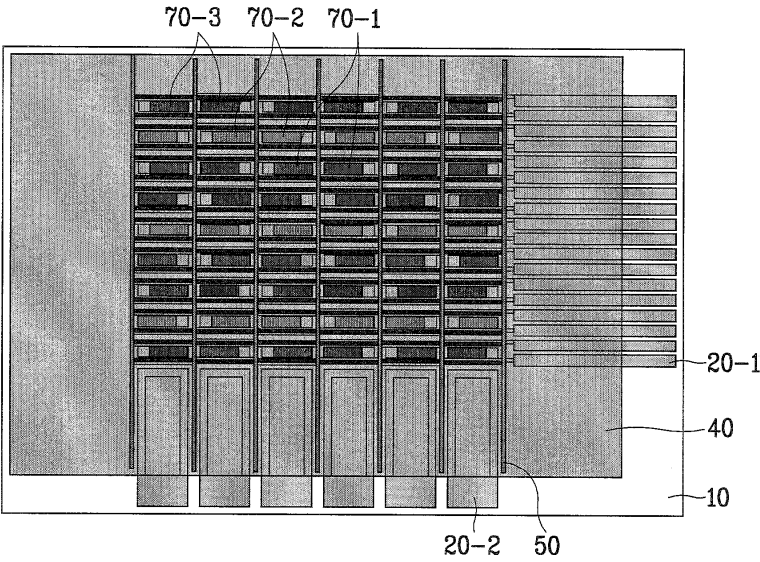


5f

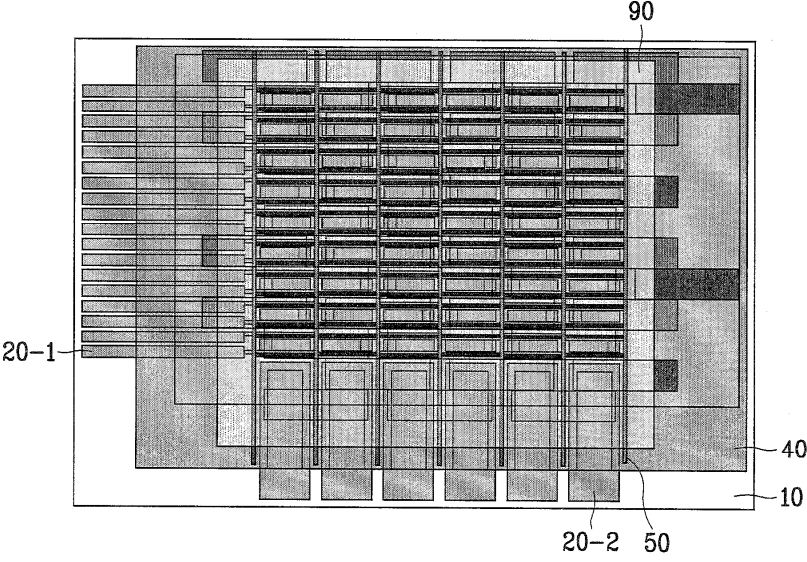




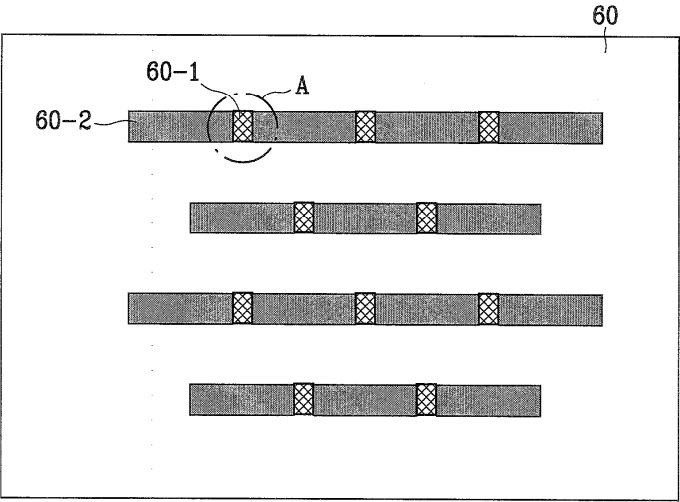
5g



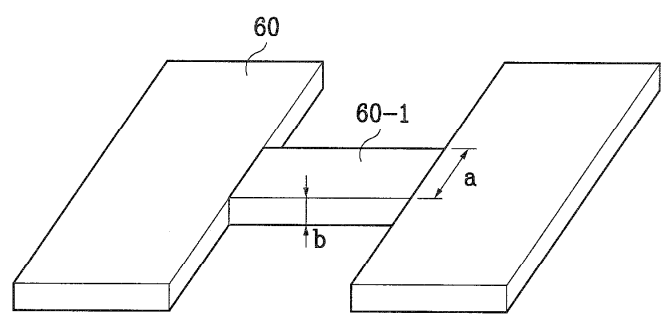
5h



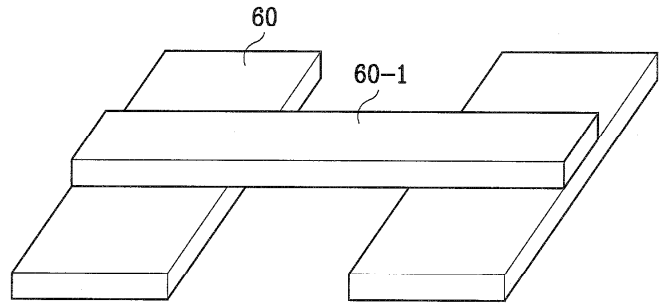
6



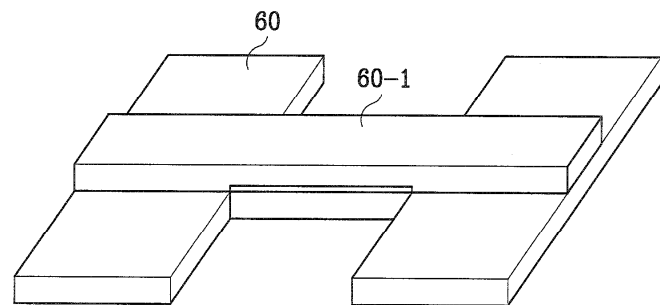
7a



7b

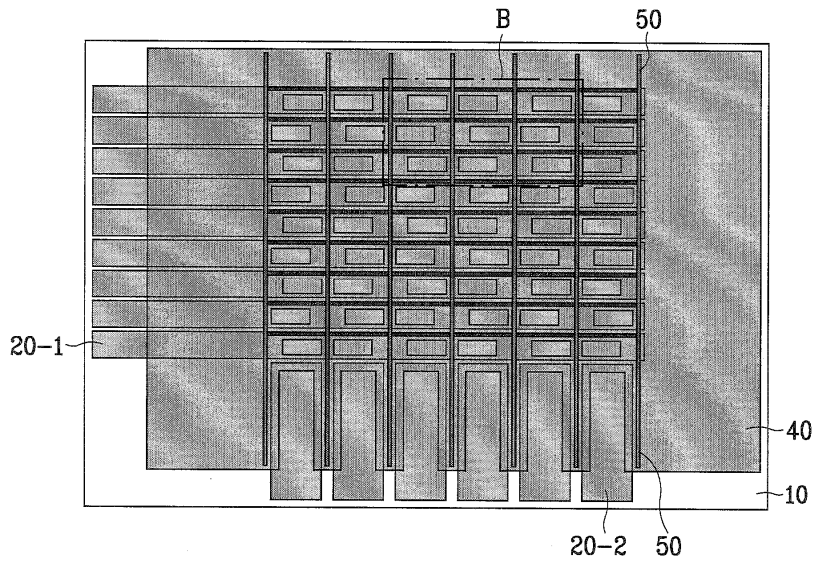


7c

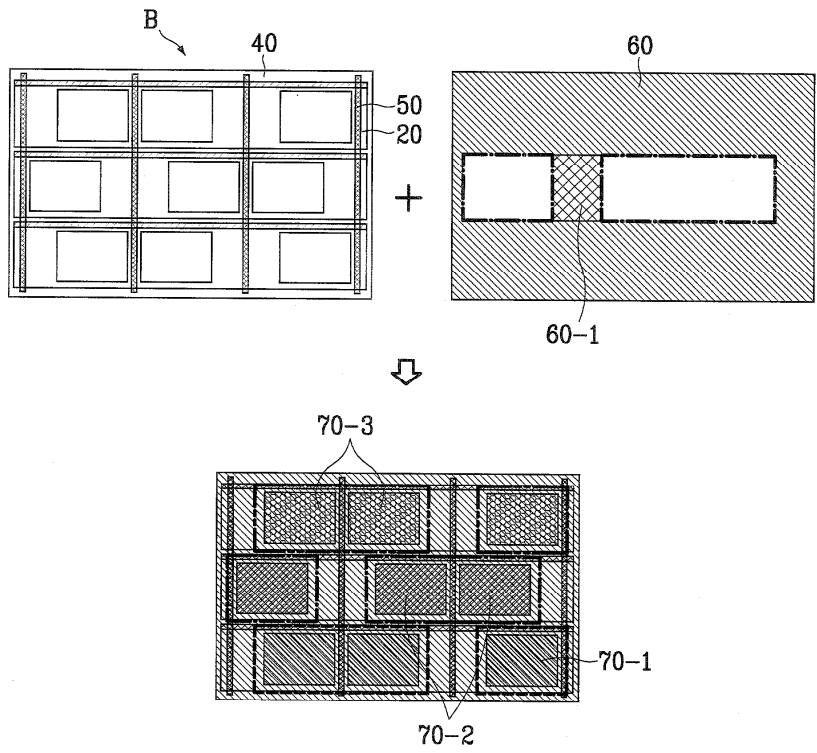




8



9



专利名称(译)	阴影掩模和使用该阴影掩模的全色有机EL显示元件		
公开(公告)号	<a href="#">KR1020030081737A</a>	公开(公告)日	2003-10-22
申请号	KR1020020020102	申请日	2002-04-12
申请(专利权)人(译)	LG电子公司		
当前申请(专利权)人(译)	LG电子公司		
[标]发明人	KIM CHANGNAM		
发明人	KIM,CHANGNAM		
IPC分类号	H01L51/50 C23C14/04 H05B33/10		
CPC分类号	H01L51/0011 C23C14/042 H01L27/3283 H01L27/3211		
代理人(译)	金勇 新昌		
其他公开文献	KR100469252B1		
外部链接	<a href="#">Espacenet</a>		

#### 摘要(译)

本发明涉及提供荫罩和使用该荫罩的全色有机电致发光显示装置。并且它由具有条形孔图案的薄膜板形成，其中荫罩沿特定方向多个排列。它具有这样的结构，其中形成每两个像素空间一个的桥，使得孔图案具有两个像素间隔尺寸。以这种方式，它可以防止由荫罩的张力引起的变形下垂。并且，如果在采用包括全色有机电致发光显示装置等的平板显示面板的像素阵列方法中采用条带类型时使用上述阴影掩模，则有利于有机发光层沉积。像素的孔径比增强。可以降低器件的驱动电压。影子面具。

